

Version with markings to show changes made

IN THE SPECIFICATION:

The following paragraph has been inserted at page 1, line 3:

PRIORITY REFERENCE TO PRIOR APPLICATION

This application claims benefit under 35 U.S.C. §119 of Korean patent application number 10-2002-0061654, entitled "Ternary Block Copolymer and Manufacturing Method of the Same," filed on October 10, 2002, by inventors Kwanyoung Lee, Young Jin Kim and Jong-geun Kim.